

Design activities towards stitched sensor

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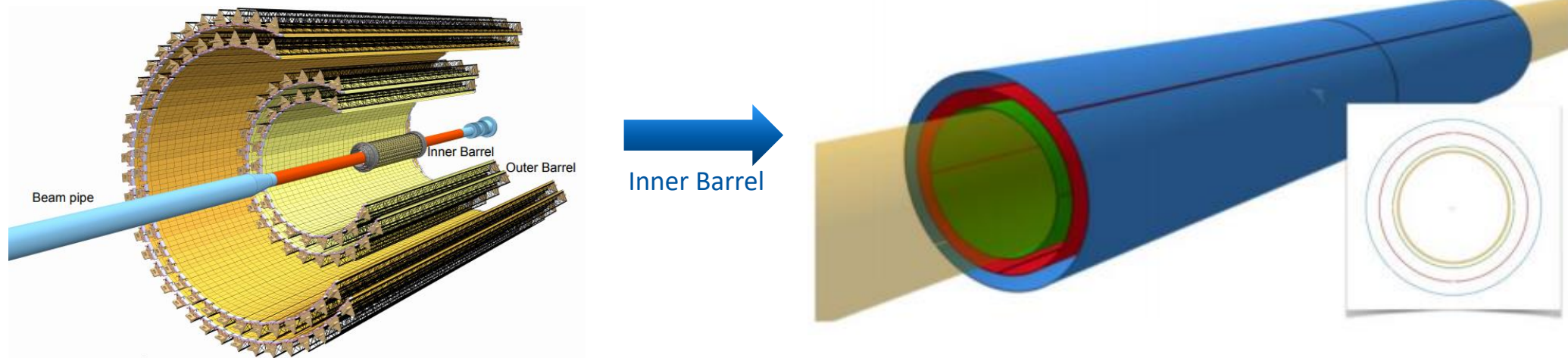
Yonsei University

Outline



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 - ITS3 timeline
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 - Chip production
 - TTS Measurement
- ER1
 - MOSS Monolithic Stitched Sensor
 - Digital pixel implementation
- Next generation sensor design for LS3

Introduction



"Technical Design Report for the Upgrade of the ALICE Inner Tracking". ALICE Collaboration, B. Abelev et al. System. J. Phys. G 41, 087002 (2014).

https://indico.ph.liv.ac.uk/event/2/contributions/144/attachments/94/125/MBuckland_ALICE_HEPXmasMeeting.pdf

- ITS3 detector concept

- The inner barrel in ITS2 is ultra-light but rather packed and irregular
- circuit board (power&data) / mechanical support / water cooling
- Integrating on chip / Rolling Si Wafer / power consumption below 20mW/cm²

https://indico.cern.ch/event/932973/contributions/4073514/attachments/2141373/3608219/2020-11-12_FCC_ALICE_MAPS.pdf

ITS3 detector concept

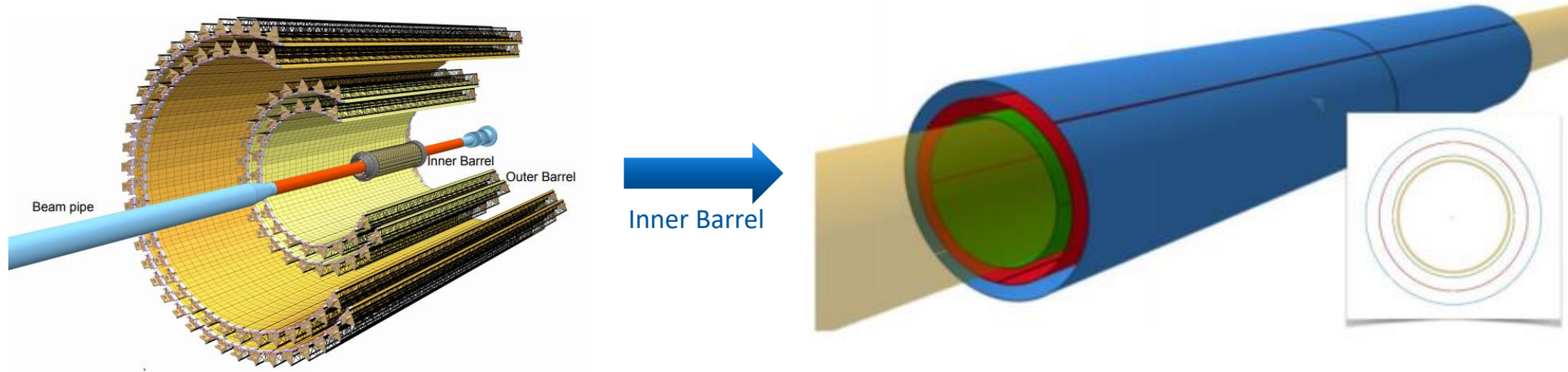
Parameter	ALPIDE (existing)	Wafer-scale sensor (this proposal)
Technology node	180 nm	65 nm
Silicon thickness	50 μm	20-40 μm
Pixel size	27 x 29 μm	O(10 x 10 μm)
Chip dimensions	1.5 x 3.0 cm	scalable up to 28 x 10 cm
Front-end pulse duration	$\sim 5 \mu\text{s}$	$\sim 200 \text{ ns}$
Time resolution	$\sim 1 \mu\text{s}$	$< 100 \text{ ns}$ (option: $< 10 \text{ ns}$)
Max particle fluence	100 MHz/cm ²	100 MHz/cm ²
Max particle readout rate	10 MHz/cm ²	100 MHz/cm ²
Power Consumption	40 mW/cm ²	$< 20 \text{ mW/cm}^2$ (pixel matrix)
Detection efficiency	$> 99\%$	$> 99\%$
Fake hit rate	$< 10^{-7}$ event/pixel	$< 10^{-7}$ event/pixel
NIEL radiation tolerance	$\sim 3 \times 10^{13}$ 1 MeV n _{eq} /cm ²	10^{14} 1 MeV n _{eq} /cm ²
TID radiation tolerance	3 MRad	10 MRad

https://indico.cern.ch/event/813597/contributions/3727803/attachments/1989307/3315951/2020-02-18_Trento2020 ITS3.pdf

- Chip size is traditionally limited by CMOS manufacturing (“reticle size”)
 - typical sizes of few cm²
 - modules are tiled with chips connected to a flexible printed circuit board
- New option: **stitching**, i.e. aligned exposures of a reticle to produce larger circuits
 - actively used in industry
 - a 300 mm wafer can house a chip to equip a full half-layer

https://indico.cern.ch/event/813597/contributions/3727803/attachments/1989307/3315951/2020-02-18_Trento2020 ITS3.pdf

ITS3 detector concept



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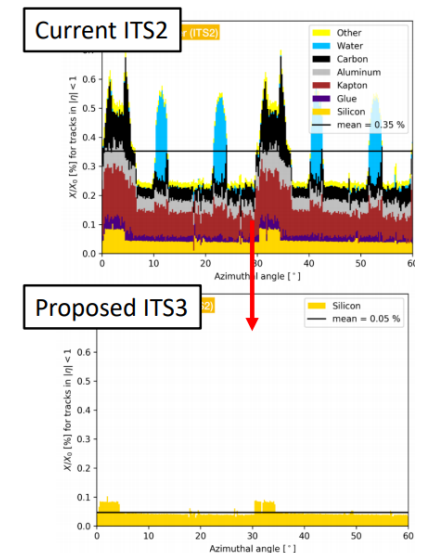
- **Key ingredients:**

- 300 mm wafer-scale chips, fabricated using stitching
- thinned down to 20-40 μm (0.02-0.04% X_0), making them flexible
- bent to the target radii
- mechanically hold in place by carbon foam ribs

- **Key benefits:**

- extremely low material budget: 0.02-0.04% X_0 (beampipe: 500 μm Be: 0.14% X_0)
- homogeneous material distribution: essentially zero systematic error from material distribution

https://indico.cern.ch/event/974424/contributions/4158313/attachments/2185864/3693273/2021-02-08_DQFEET-ITS3sensor.pdf



ITS3 timeline

main milestones

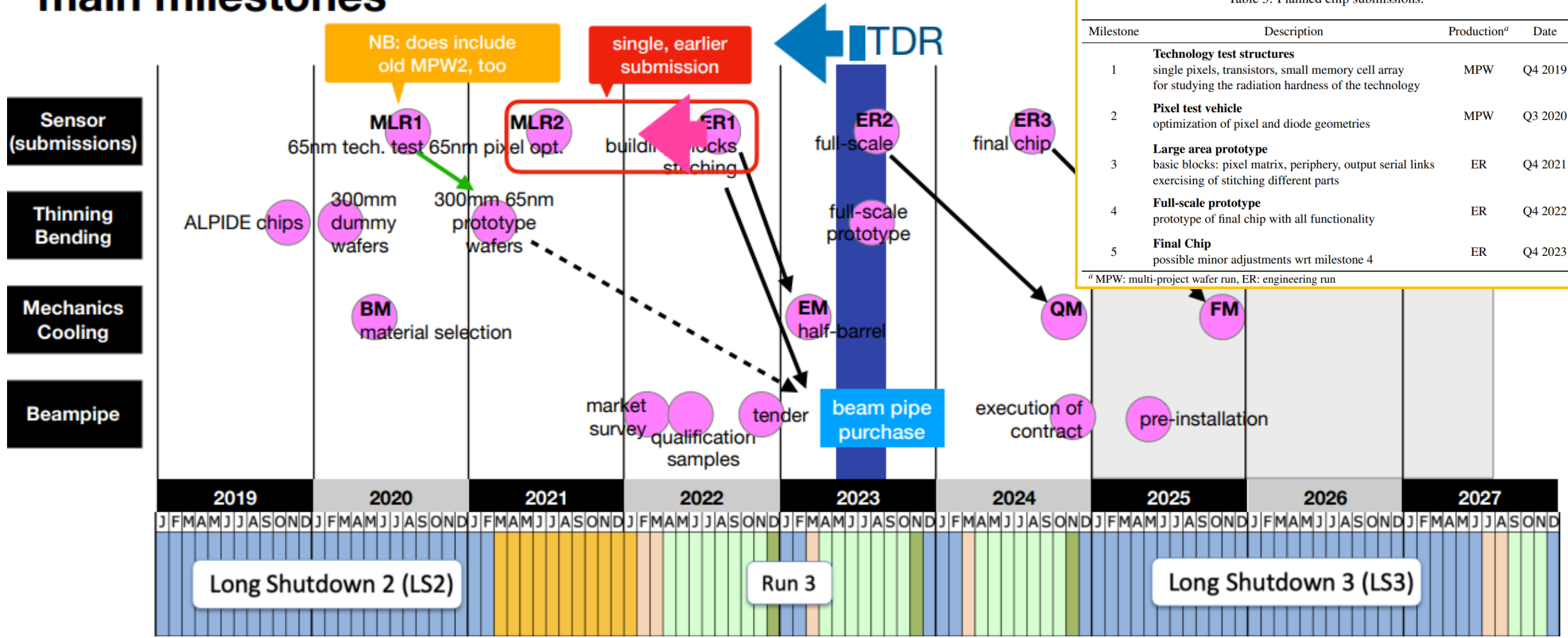


Table 3: Planned chip submissions.

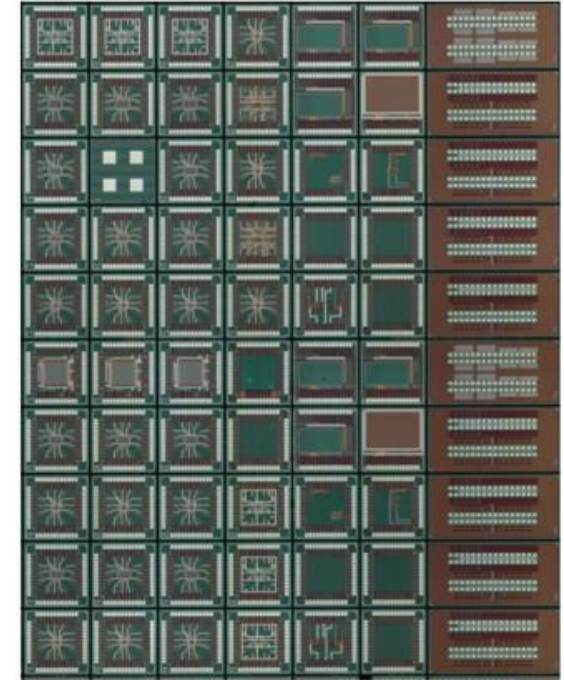
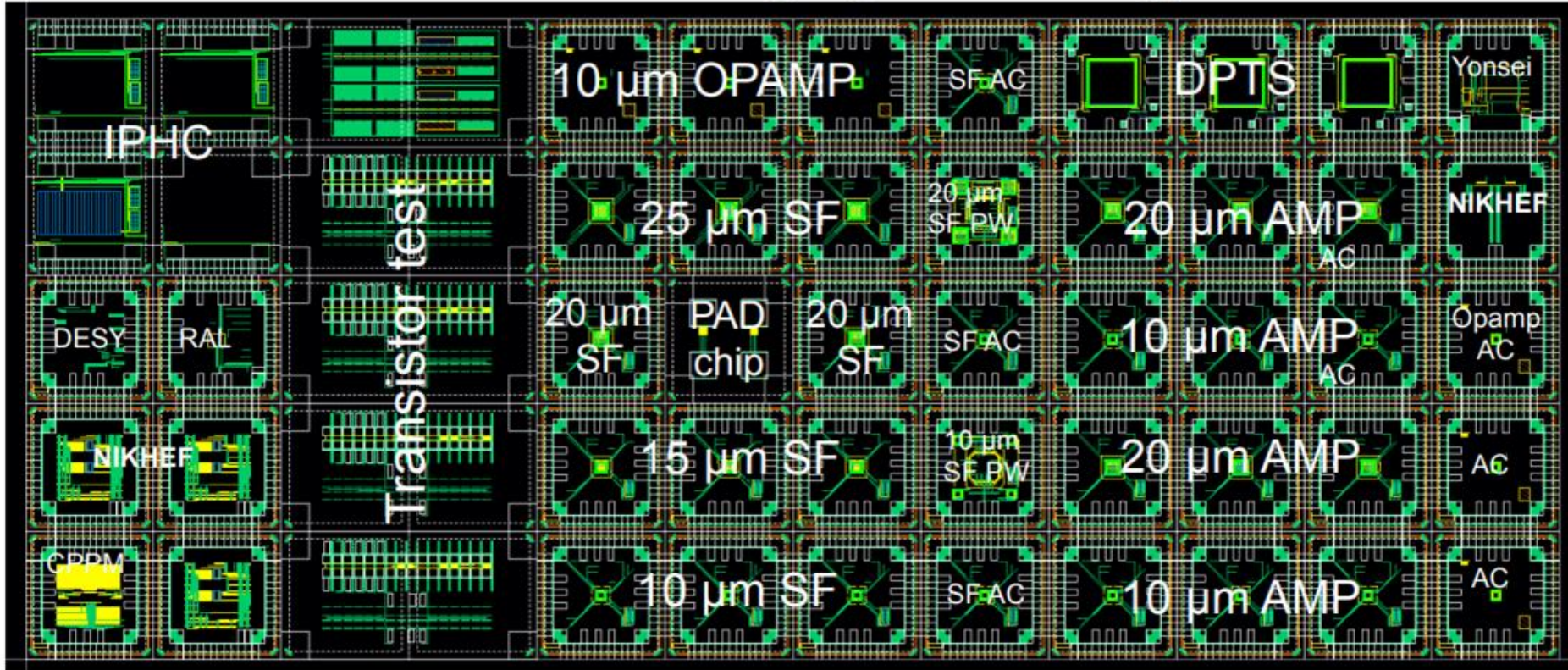
Milestone	Description	Production ^a	Date
1	Technology test structures single pixels, transistors, small memory cell array for studying the radiation hardness of the technology	MPW	Q4 2019
2	Pixel test vehicle optimization of pixel and diode geometries	MPW	Q3 2020
3	Large area prototype basic blocks: pixel matrix, periphery, output serial links exercising of stitching different parts	ER	Q4 2021
4	Full-scale prototype prototype of final chip with all functionality	ER	Q4 2022
5	Final Chip possible minor adjustments wrt milestone 4	ER	Q4 2023

^a MPW: multi-project wafer run, ER: engineering run

Tight schedule, but we are on track!

MLR: multiple layer per reticle, **ER:** engineering run,
BM: breadboard module, **EM:** engineering module, **QM:** qualification module, **FM:** final module

MLR1 production

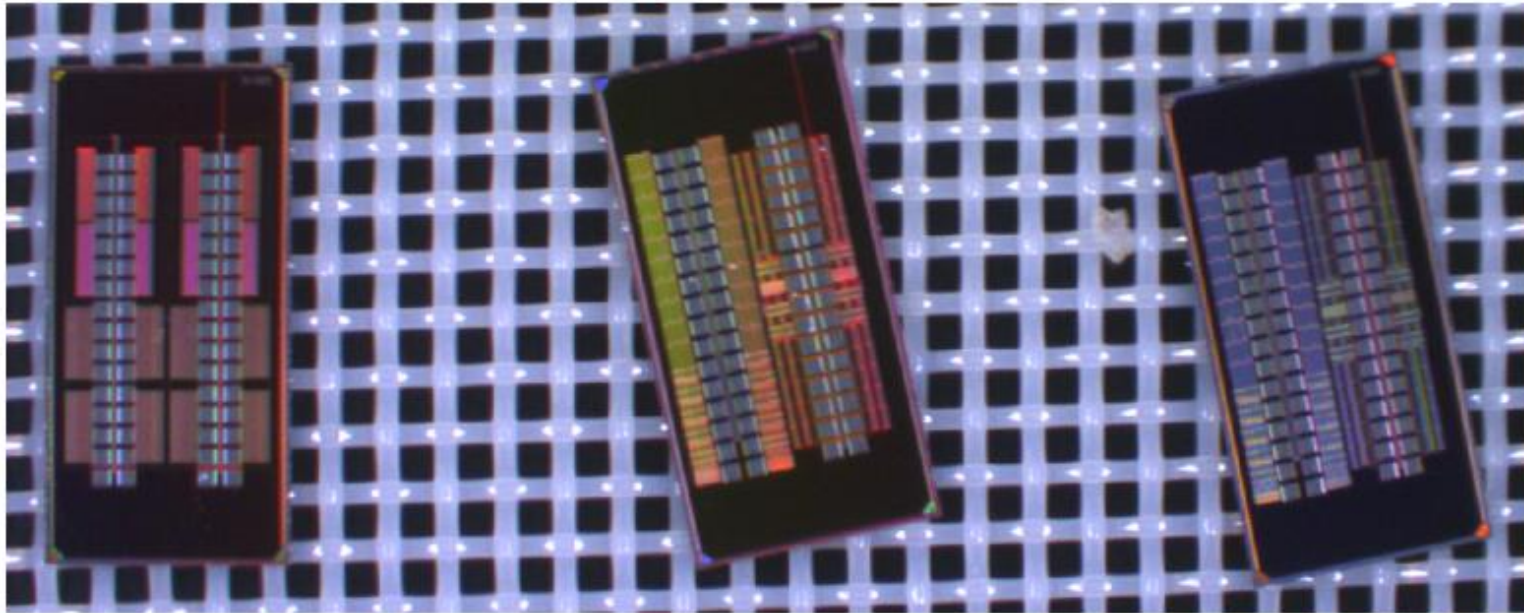


- GDS submission in Dec 2020
- Chip delivery in July 2021

65 nm prototypes, MLR1

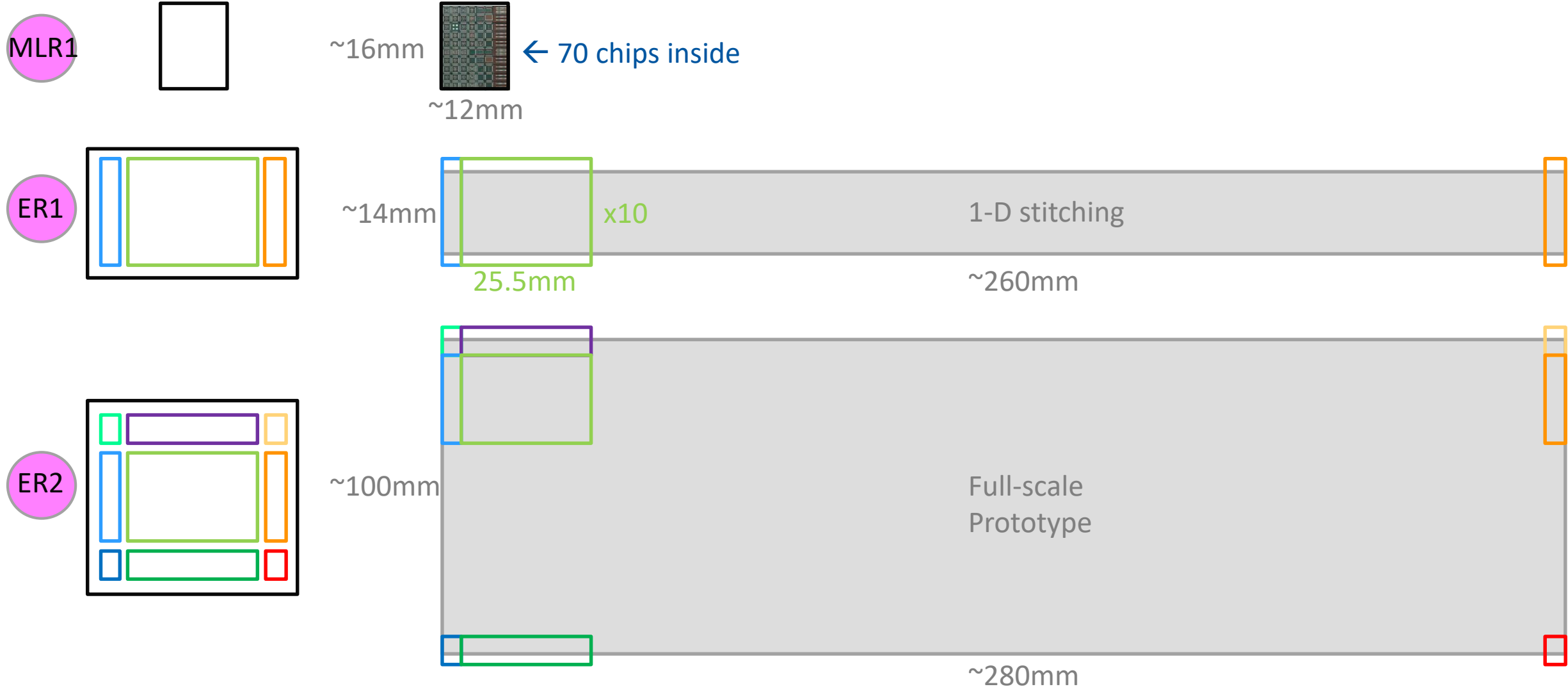
transistor test structures

- ▶ Compatible with existing test system based on probe card
- ▶ Tests have already started
 - no apparent showstoppers so far
 - detailed analysis ongoing and in discussion with foundry

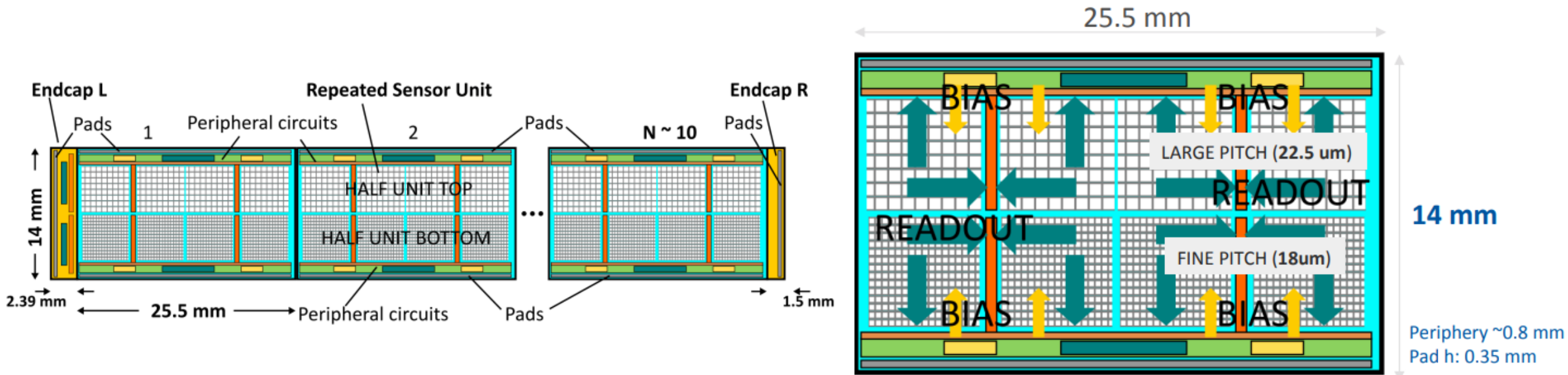


Very encouraging results, clears first milestone of 65 nm verification

Stitched sensor development

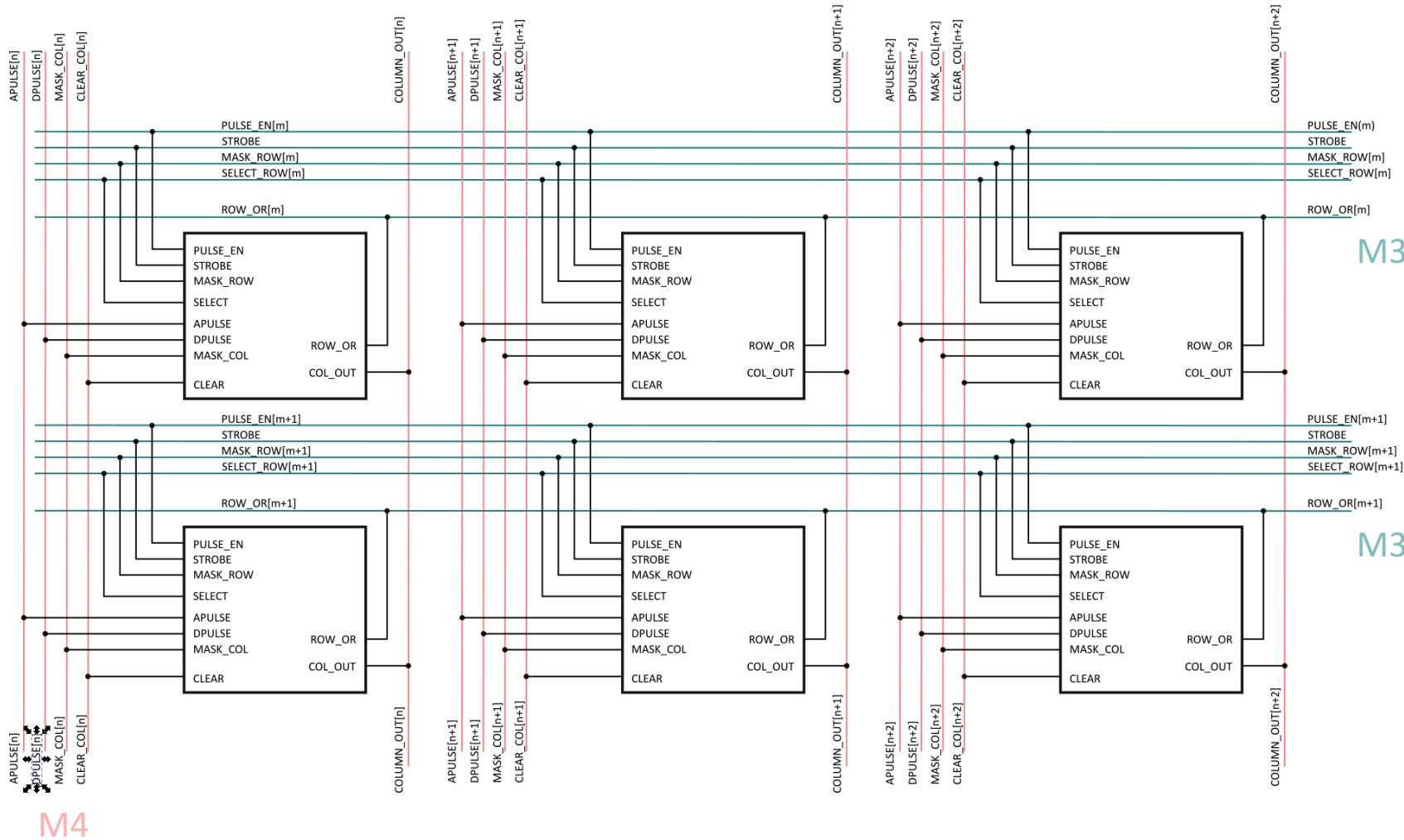


MOSS Monolithic Stitched Sensor Prototype



- Implement a large sensor abutting identical but functionally independent sub-units
 - Repeated Sensor Unit, Endcap Left, Endcap Right
 - Stitching used to connect metal traces for **power distribution** and **long range on-chip interconnect busses for control and data readout**

Concept for Pixels Readout in a Region



Global Strobe

In-Pixel Latch

Row OR output line

M3

Selection of row (token)

Skip rows with no hits

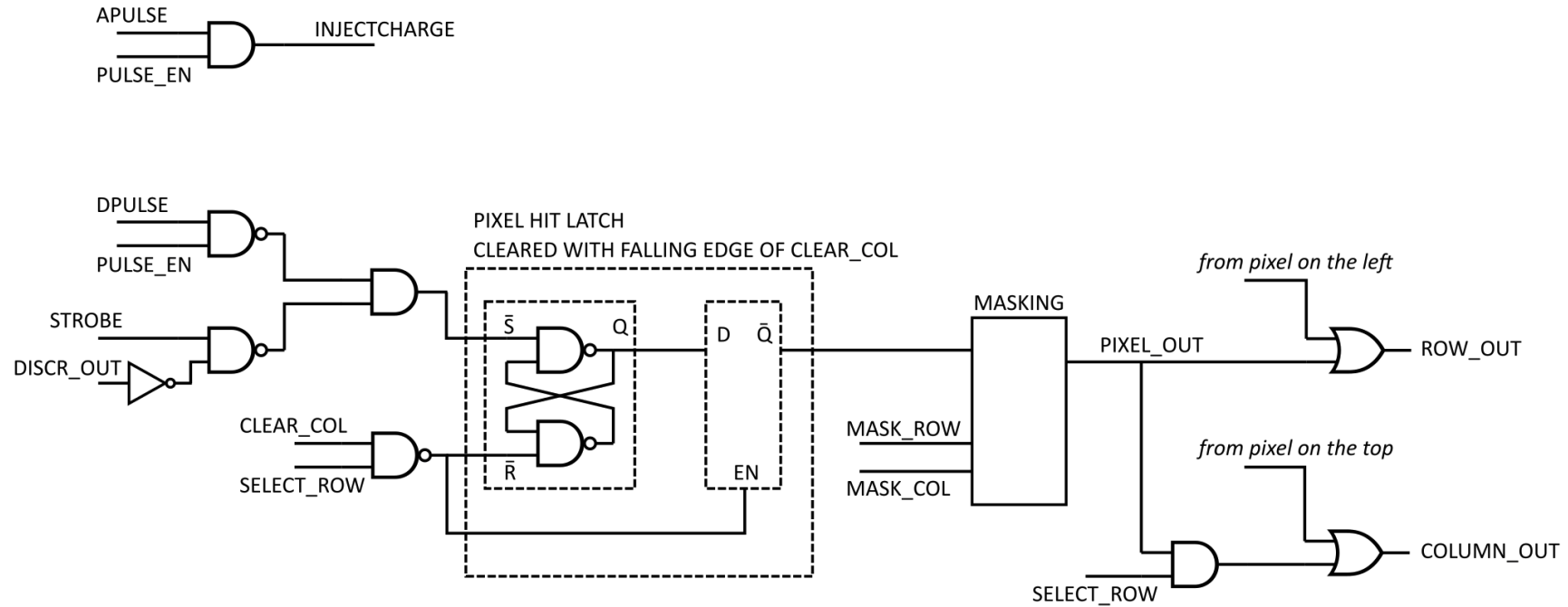
Column out line

Pixels of the selected row drive the column line

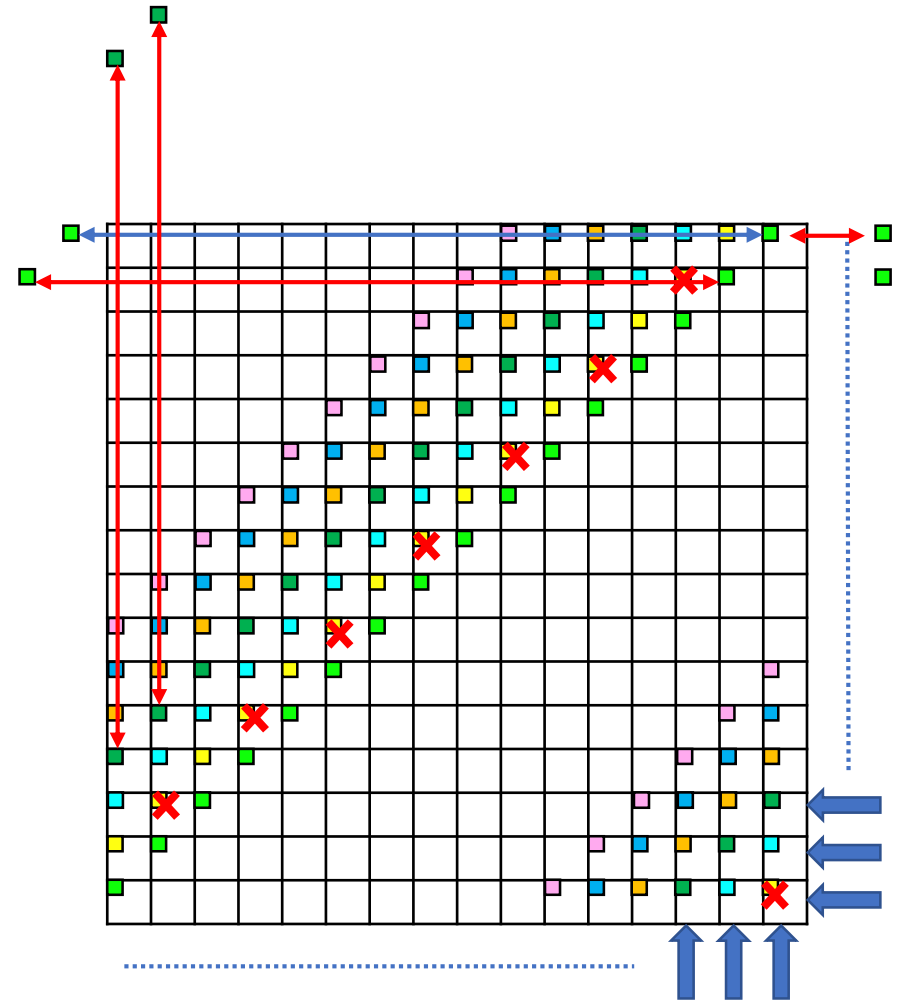
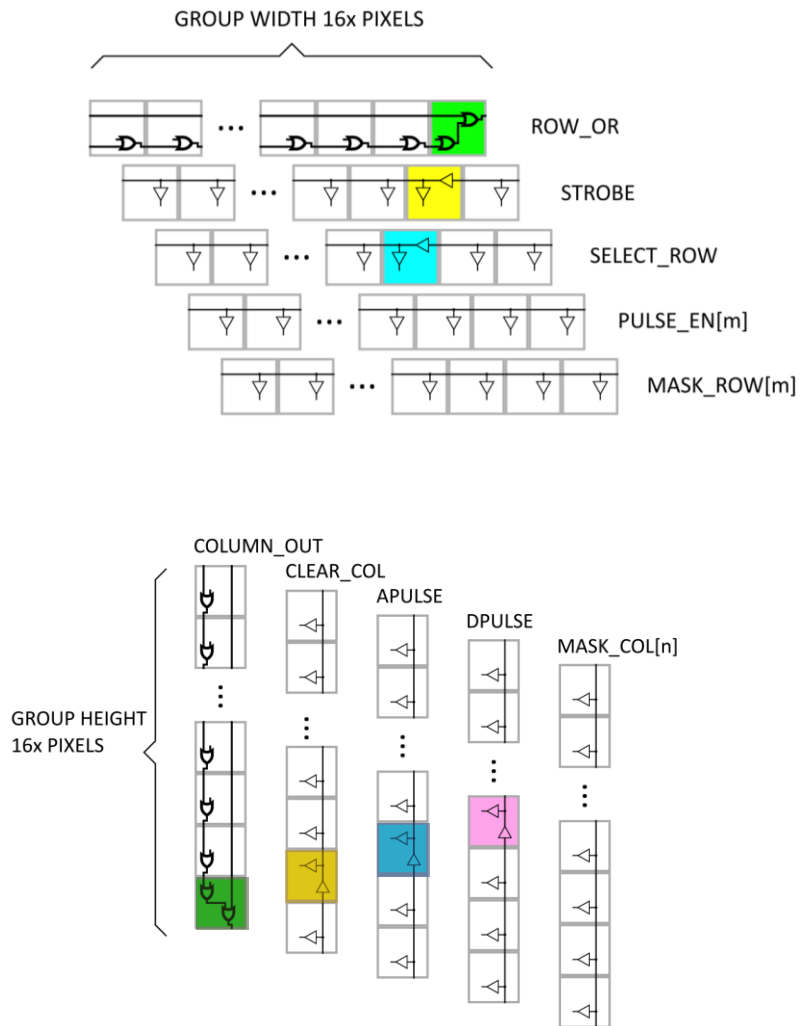
M3

M4

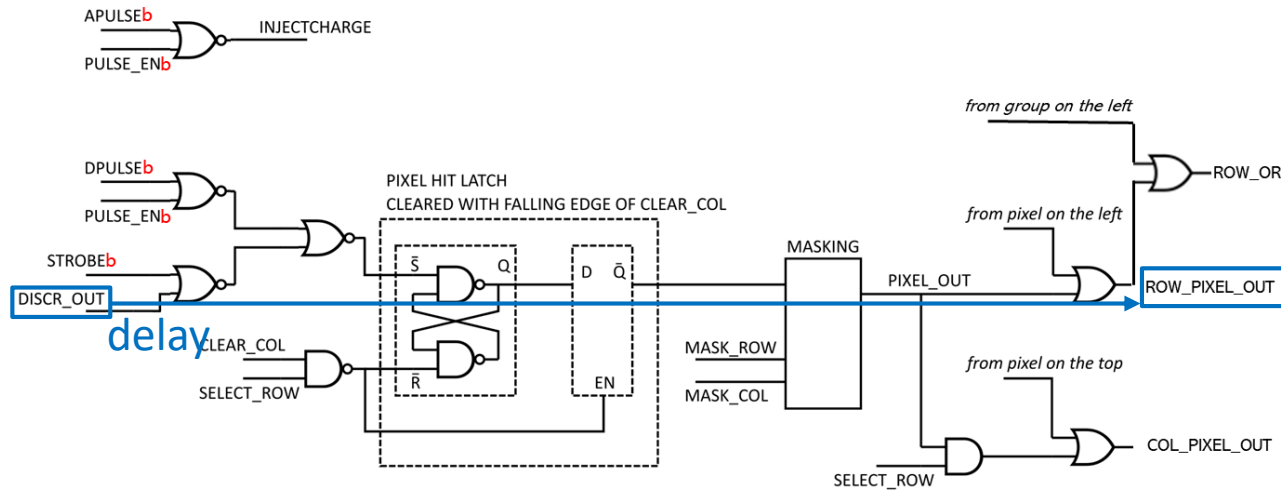
Digital pixel logic



Signal Regeneration



Post-layout extraction simulation results



PWELL=0 V

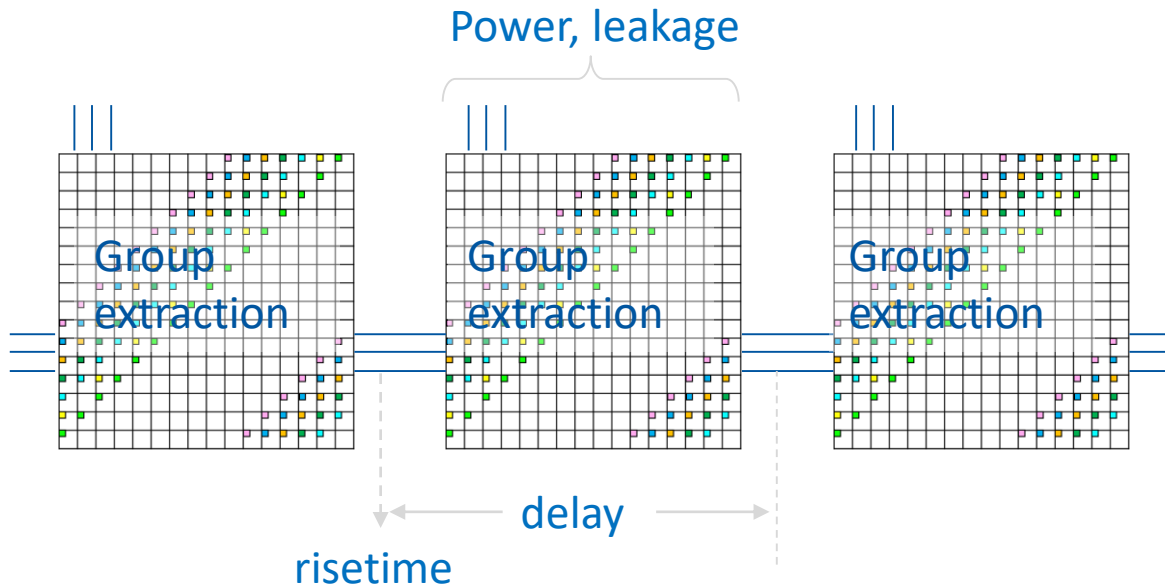
Typical corner (1.2V, typical process, 27degrees)

- Output delay
(FE output over Vth 0.6V → ROW_PIXEL_OUT) : 24 ns
(ROW_PIXEL_OUT → ROW_OR) : 1.022ns
(ROW_OR → ROW_OR) : 0.612ns

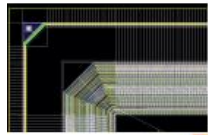
- STROBE group-to-group delay 0.719ns
- STROBE regeneration dynamic energy 84.1 fJ
- SELECT_ROW group-to-group delay 1.21ns

- Pixel digital
Dynamic energy 2.32pJ
Static energy 16.2fJ for 5us
Static leakage current 2.71nA

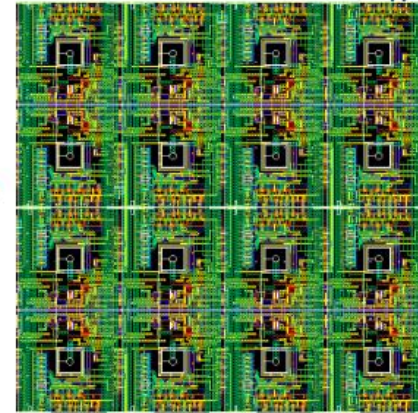
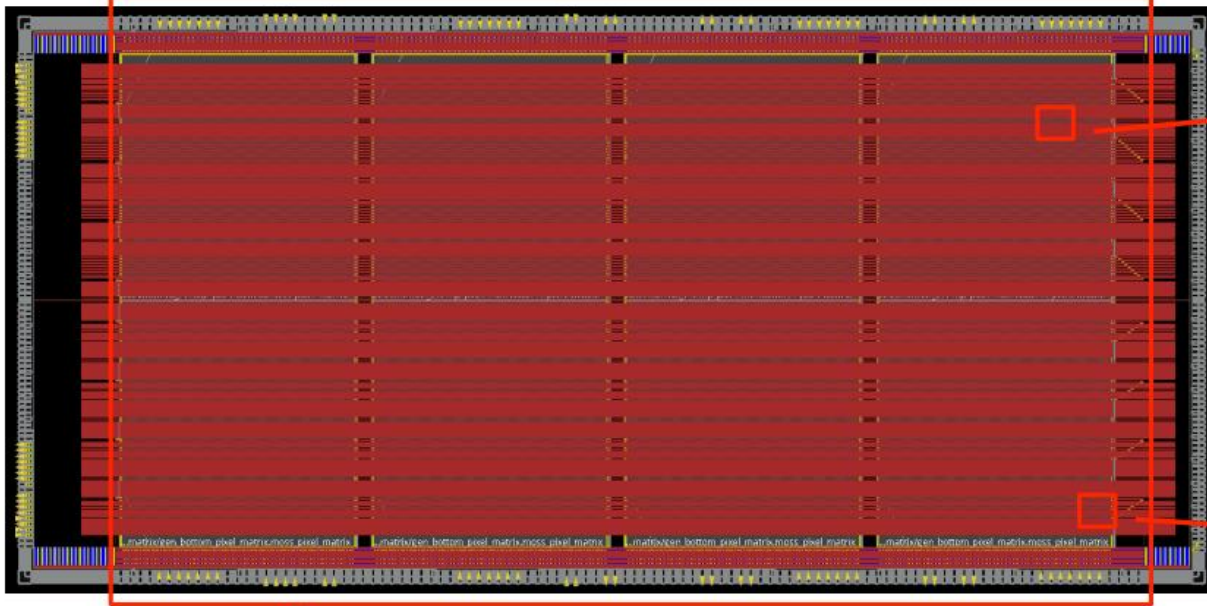
- Group digital
Static energy 3.65pJ for 5us
Static leakage current 608nA



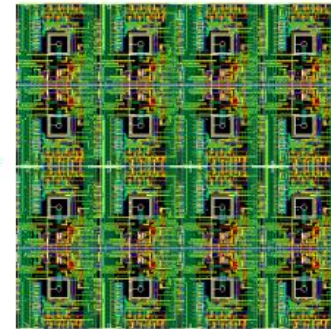
Pre-mock submission – Dec 2021



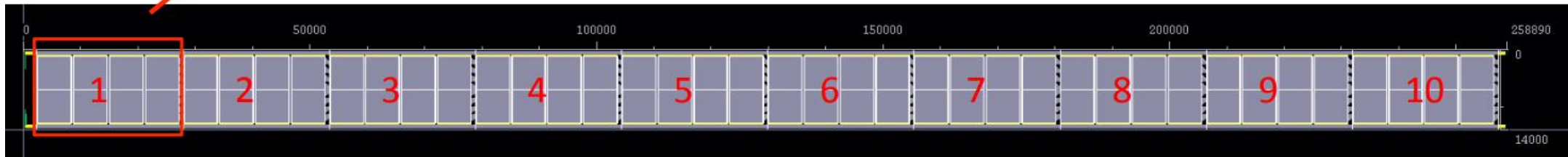
1 of 10



Pitch
22.5 um



Pitch
18 um



Next generation sensor design for LS3

- Good timing (10's of ps ?)
 - Avalanche photodiode
 - Digital operation without the analog front end
- High spatial resolution
 - Pixel detector
- Low power consumption
 - Low digital activity (\sim low occupancy)
 - Digital periphery with the sparcified readout
- Simple operation
 - Built-in tolerance in the APD operation

Digital pixel coupled with low gain APD

- Thick epitaxial layer of about 25 μm for charge collection

$$Q_{Gen} = 0.1 \cdot 50e/\mu\text{m} \cdot 25\mu\text{m} = 0.1 \cdot 1250e = 125e = 2.0 \cdot 10^{-17} \text{C}$$

- Low gain APD ($m = 50$)

$$Q_{Col} = m \cdot Q_{Gen} = 1.0 \cdot 10^{-15} \text{C}$$

- Collection electrode with small capacitance

$$C = 3.2 \text{ fF}$$

- 1.2(V) LVCMOS digital pixel operation

$$V_{Sig} = \frac{Q_{Col}}{C} = 0.313 \text{ V} > V_{th} = 0.3 \text{ V}$$

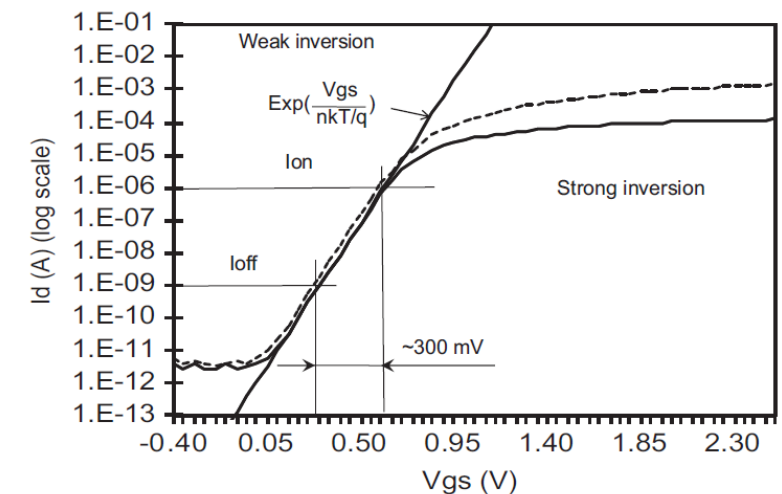
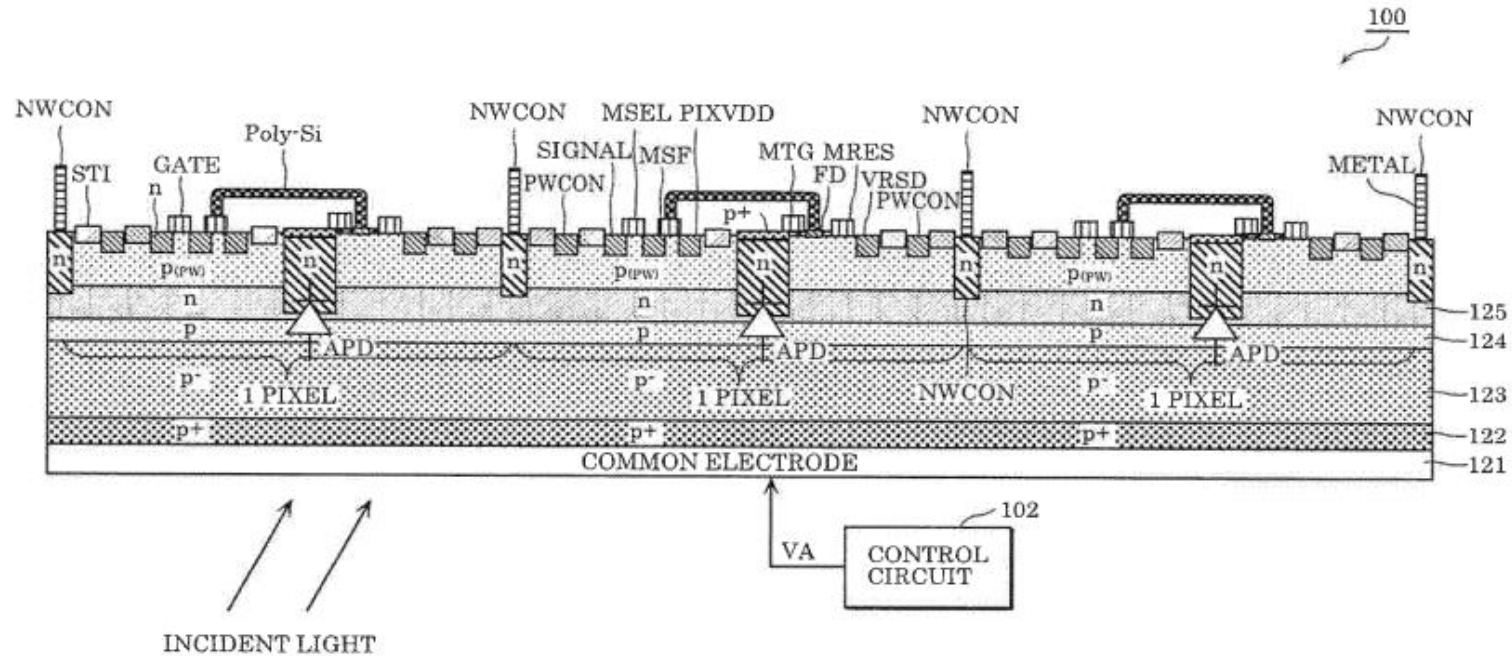
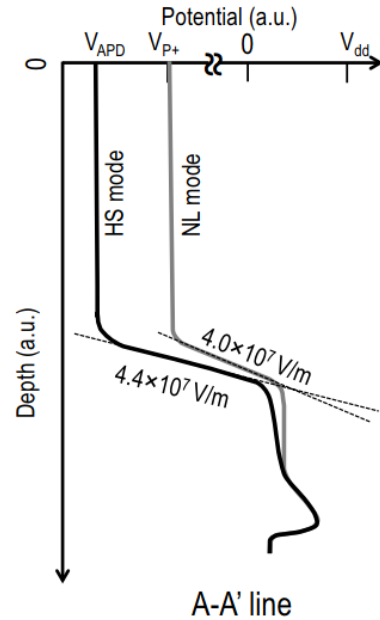
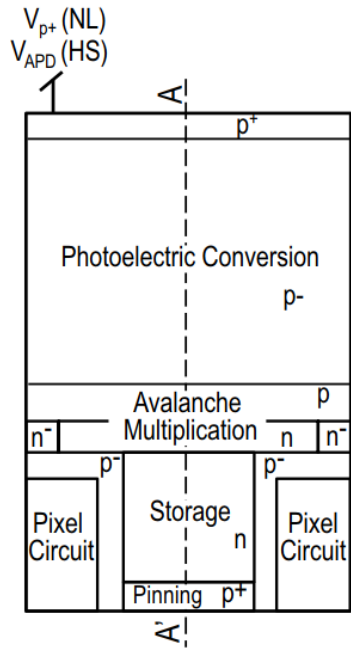


Fig. 4. Log(I_d) vs V_{gs} for an example transistor, 300 mV are necessary to increase the current by a factor 1000.

Snoeys, W. "CMOS monolithic active pixel sensors for high energy physics." Nuclear Instruments and Methods in Physics Research Section A 2014

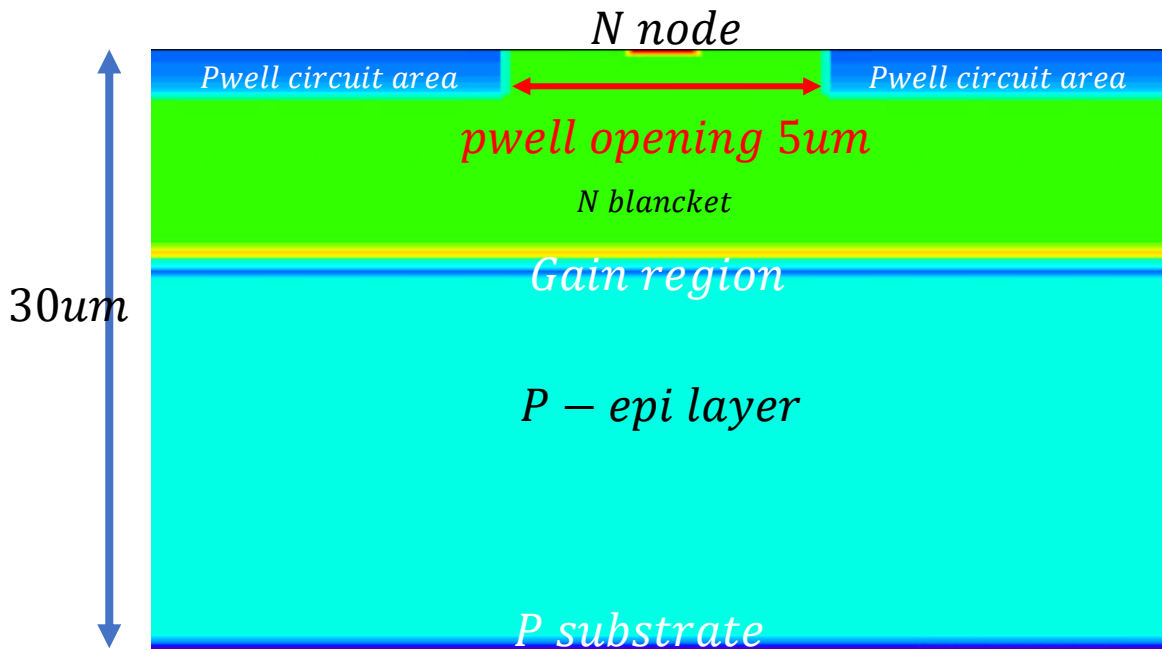
Publications of interest



- 3.8um pixel
- Normal mode / High-sensitivity mode
- Abrupt p-n junction between a p- region and n region
- Vertical field strength is controlled by the potential of a surface p+ layer (either V_{p+} or V_{APD})

Mori, Mitsuyoshi, et al. "6.6 A 1280× 720 single-photon-detecting image sensor with 100dB dynamic range using a sensitivity-boosting technique." 2016 IEEE ISSCC
 Patent EP 3448018A1 - PANASONIC 2019

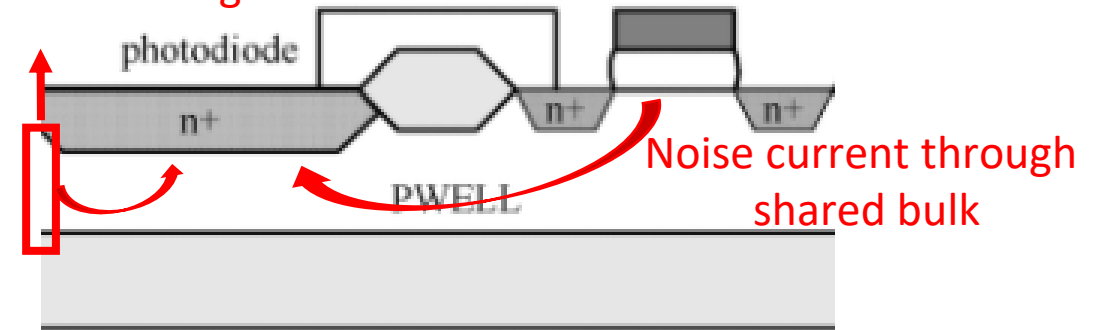
APD into the pixel



Younghoon Han

Junction Termination Edge

Defects caused by the wafer sawing



Kiwon seo